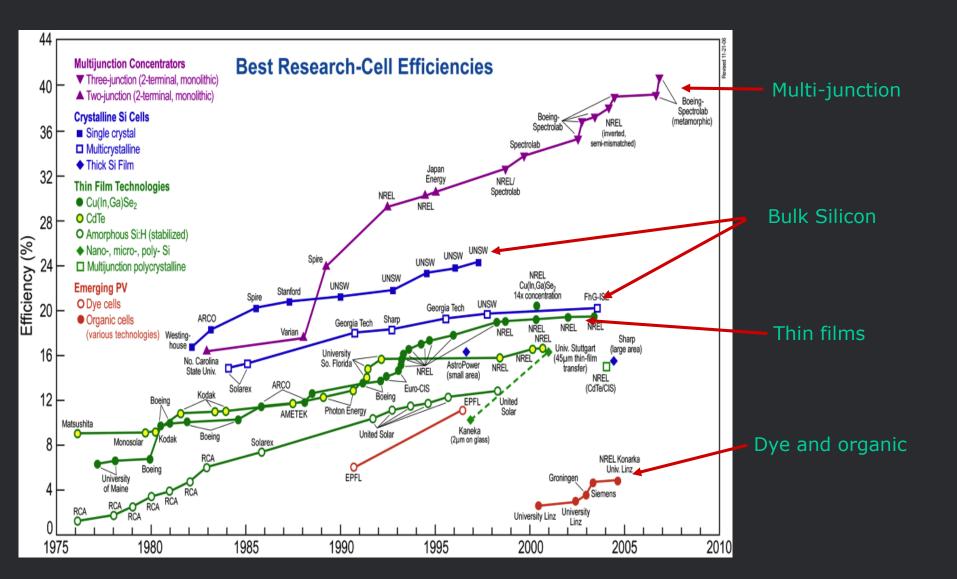
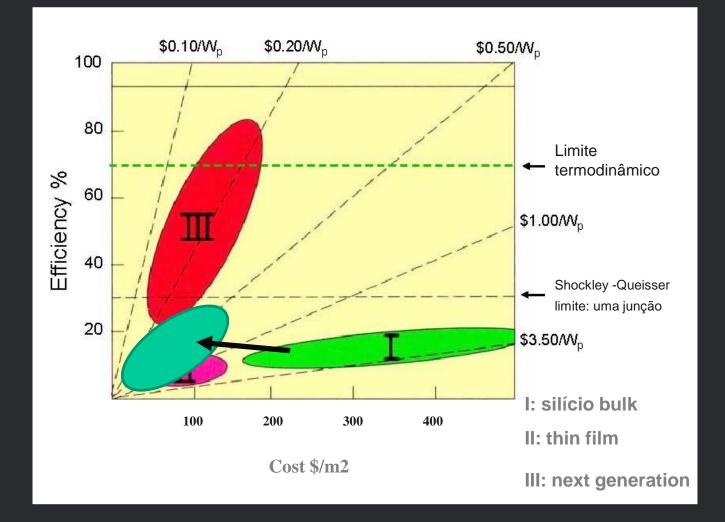
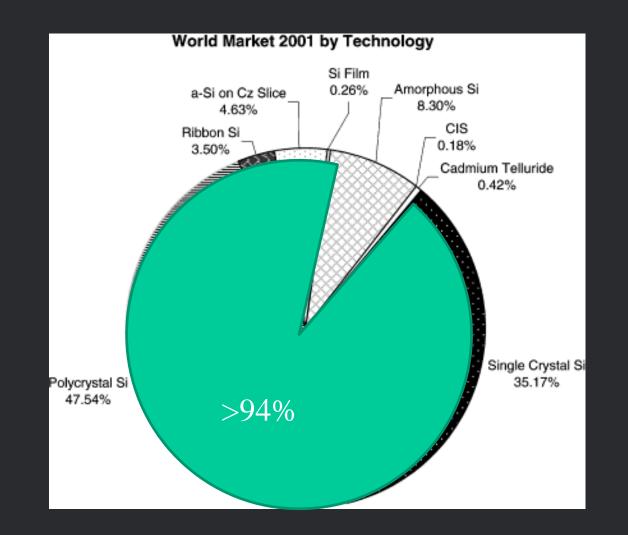
Visão da I&D no fotovoltaico



Visão da I&D no fotovoltaico



Visão da I&D no fotovoltaico



SOURCE: A. Goetzberger et al. / Materials Science and Engineering R 40 (2003)

Silicon PV flowchart



First generation

- Single layer of *p*-*n* diode
- One excitation per photon
- Mostly made of silicon wafers
- 95 % of solar cell market
- Life expectancy of >30 years
- Energy payback in 2-5 years (positive)

Second generation

"Thin-film" solar cells

- Mix of glass and ceramic with very little active semiconductor material
- Inexpensive but lower efficiency

Third generation

- No *p-n* junction
- Organic polymer cells or nanocrystal cells
- Perovskites

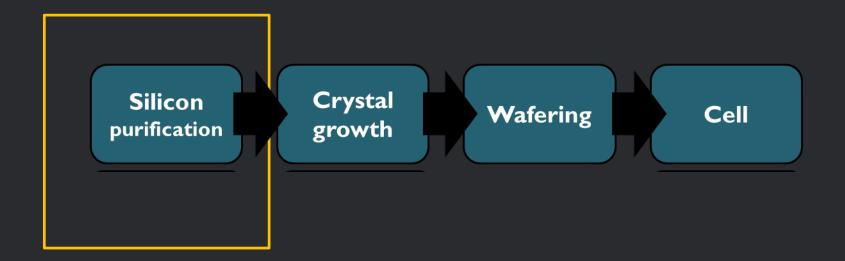
• Production of Si

• Wafer based Si solar cells

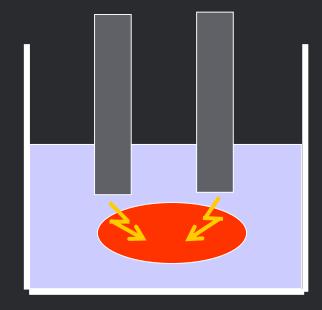
• Thin-film solar cells

• Other concepts

Silicon PV flowchart



PV Technology MG silicon



Arc furnace

MG-Si is produced by reduction of SiO2 with C in arc furnace at 1800 C

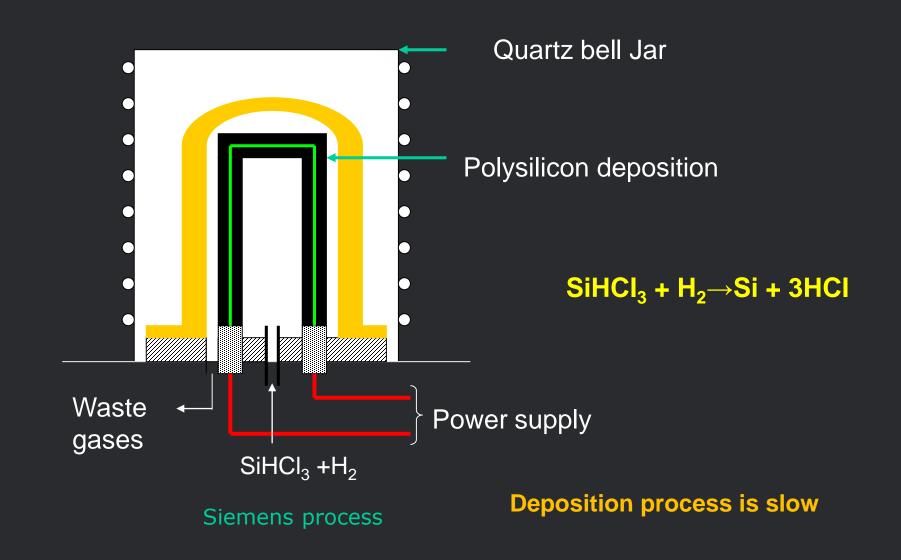
 $SiO2 + C \rightarrow Si + CO2$

PV Technology MG silicon

- MG-Si is material with 98-99% purity,
- Produced in about 1 Million tons per year
- Produced in countries which cheap electricity and quartz deposits (USA, Europe, Brazil, Australia, Norway)

• Average price is 2 to 4 \$/kg (electronic grade Si is 30-45 \$/kg)

EG silicon

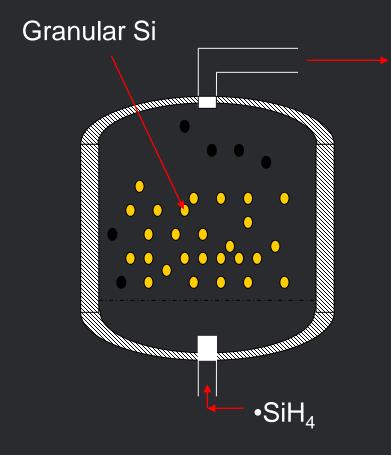


PV Technology EG silicon

Feedstock: obtaining hyperpure silicon from gas phase



PV Technology EG silicon



Fluidized bed reactor (FBR)

- Silicon seed particles are held in suspension by a gas mixture (H_2 and SiH_4)
- At 600° C gas phase decomposition takes place, causing the seed particles to grow up to 2 mm in size
- Big particles falls due to weight
- Si is collected from the bottom of the jar

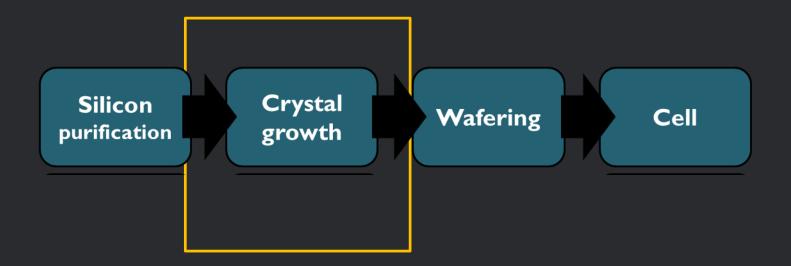
Continuous process

EG silicon

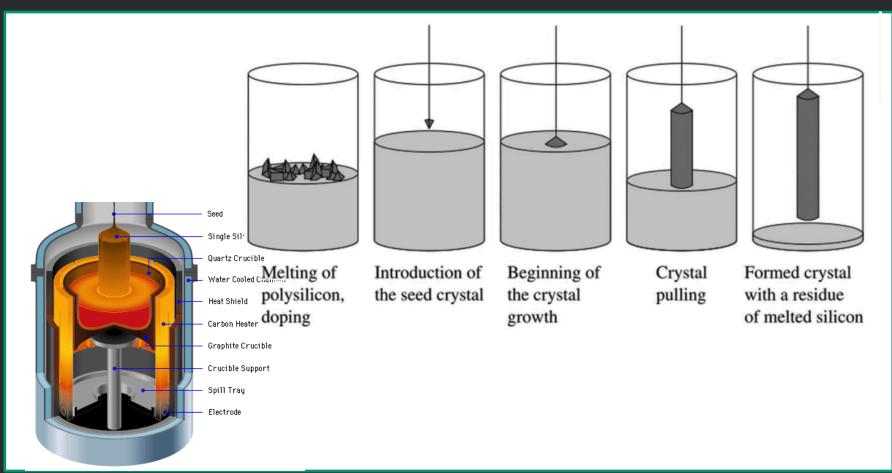
Crystalline silicon may be crystallized in PV in different forms:

| Descriptor | Symbol | Grain Size | Common Growth Techniques |
|------------------|--------|------------|-------------------------------------|
| Single crystal | sc-Si | >10cm | Czochralski (CZ) float zone (FZ) |
| Multicrystalline | mc-Si | 1mm-10cm | Cast, sheet, ribbon |
| Polycrystalline | pc-Si | 1µm-1mm | Chemical-vapour deposition |
| Microcrystalline | μc-Si | <1µm | Plasma deposition |

Silicon PV flowchart



Single crystal growth



Czochralski method

PV Technology Single crystal growth



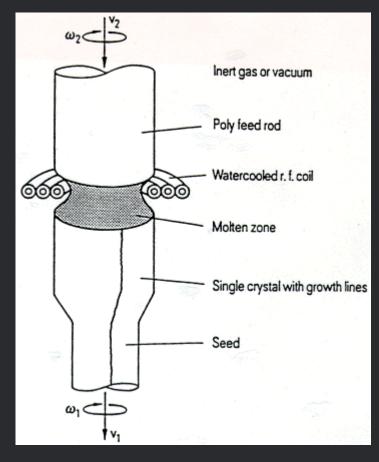
Advantages

Good crystal quality No induced thermal stresses Disadvantages

High oxygen content



Single crystal growth



Float zone method

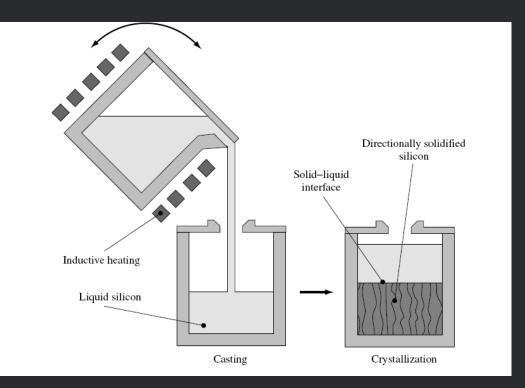
Advantages Good crystal quality No induced thermal stresses No contamination

Disadvantages

More expensive

Record efficiency solar cells have been manufactured with float zone

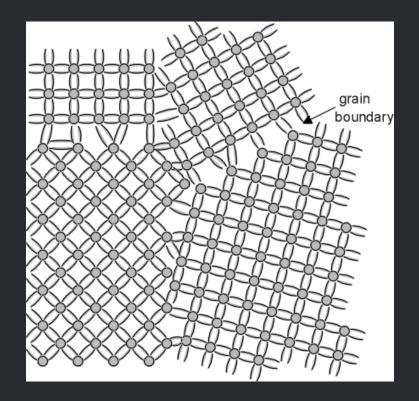
Multicrystalline silicon



Advantages Large volumes Simple **Multicrystalline** Impurity contamination **Crucible costs**

Mc silicon

Multicrystalline silicon offers acceptable quality but at lower cost



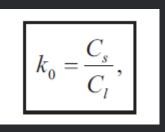


Typical casting: <u>240</u>kg/56 hours

PV Technology Bulk doping



liquid



solid

| Dopant | k_0 | Type | Dopant | k_0 | Туре |
|--------|--------------------|------|--------|----------------------|------|
| В | 8×10^{-1} | р | As | 3.0×10^{-1} | n |
| Al | 2×10^{-3} | р | Sb | 2.3×10^{-2} | n |
| Ga | 8×10^{-3} | р | Te | 2.0×10^{-4} | n |
| In | 4×10^{-4} | р | Li | 1.0×10^{-2} | n |
| 0 | 1.25 | n | Cu | 4.0×10^{-4} | a |
| С | 7×10^{-2} | n | Au | 2.5×10^{-5} | a |
| Р | 0.35 | n | | | |

^aDeep-lying impurity level.

PV Technology Bulk doping

Mo- initial weight of liquid with dopant concentration C_0 S – dopant concentration in the melt

$$-dS = C_s dM.$$

$$C_l = \frac{S}{M_0 - M}.$$

$$M-Mo$$

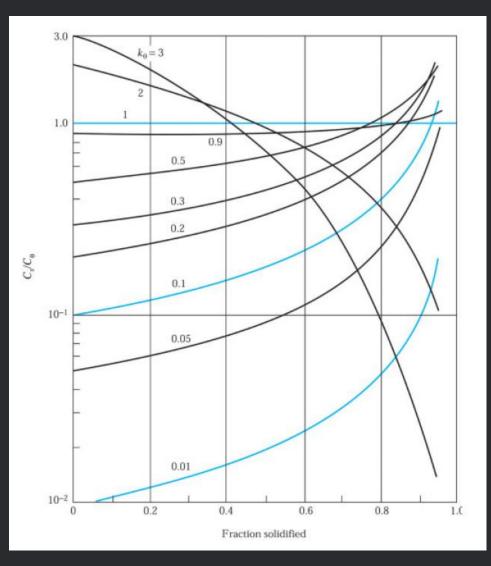
$$dM$$

$$M$$

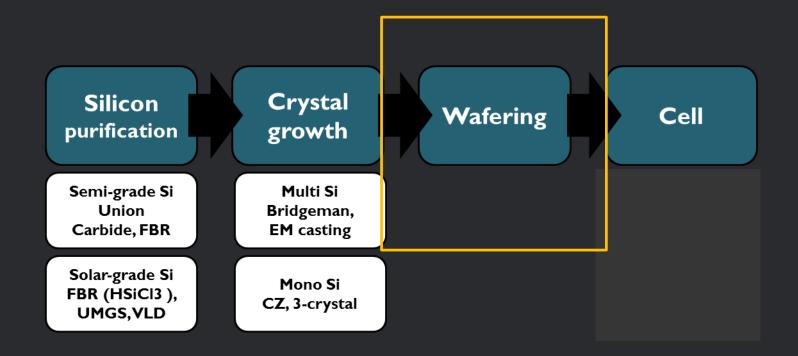
$$M$$

PV Technology Bulk doping

$$C_{s} = k_{0}C_{0}\left(1 - \frac{M}{M_{0}}\right)^{k_{0}-1}$$



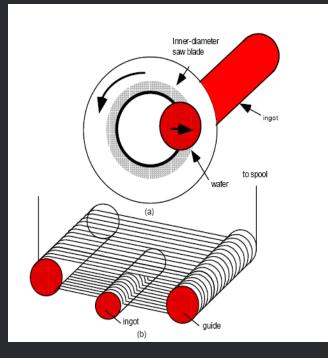
Silicon PV flowchart

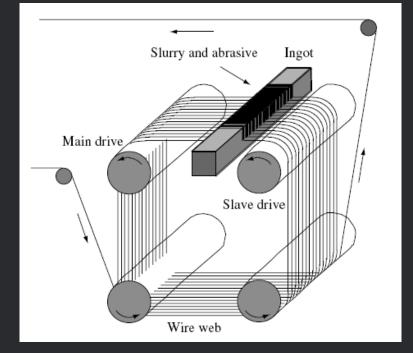


Mc silicon



PV Technology Wafering





Inner diameter sawing

Multi-wire sawing

Disadvantages

Expensive

High kerf loss

Ribbon technology

Wafering is expensive!

Reducing material consumption by: Producing thinner wafers Reducing kerf loss

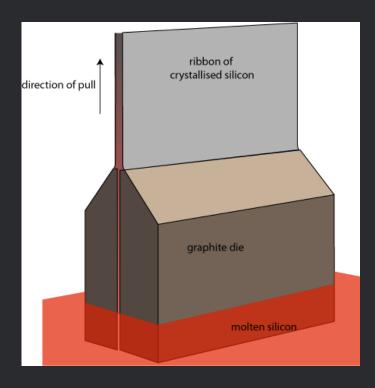
Ribbon technology

Multicrystalline wafers may be grown directly in sheet or ribbon form.

- Edge defined film fed growth (EFG)
- String ribbon (SR)
- Ribbon growth on substrate (RGS)
- Dendritic web
- Sheet silicon

•

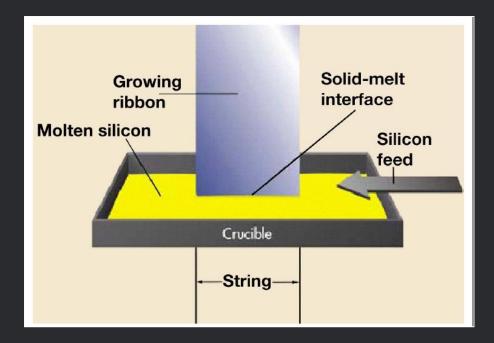
Ribbon technology





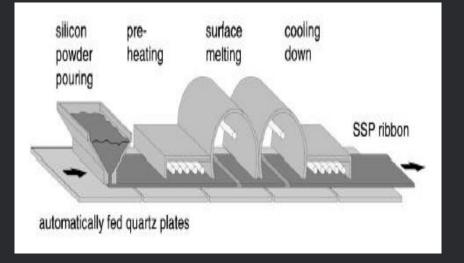


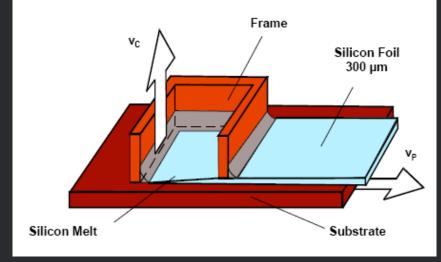
Ribbon technology



String ribbon

Ribbon technology

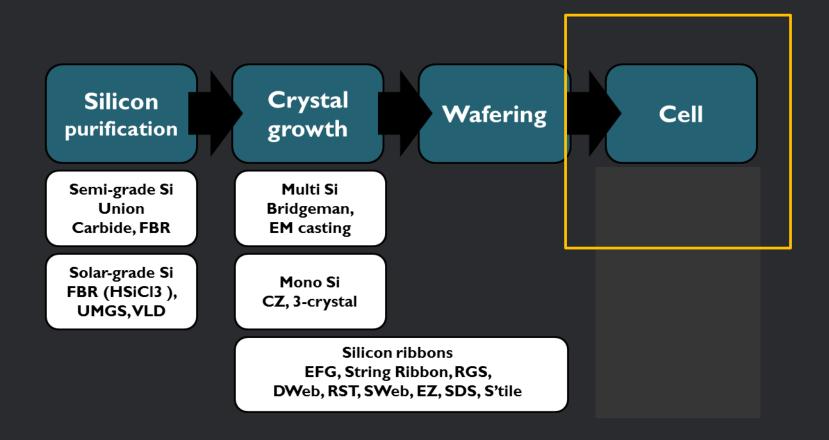






SSP

Technology overview



Technology overview

Next: Cell manufacturing